



Docket No.: N.C. 84,613

THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants : Walton et al.
Appl. No. : 10/644,567
Filed : August 20, 2003
Title : ELECTRON BEAM ENHANCED LARGE AREA DEPOSITION
SYSTEM
Art Unit : Not yet assigned
Examiner : Not yet assigned

Honorable Assistant Commissioner for Patents
Washington, DC 20231

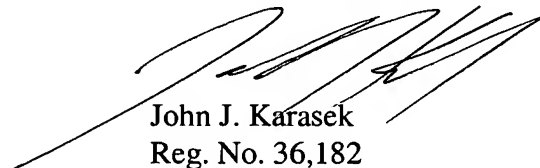
INFORMATION DISCLOSURE STATEMENT

Sir:

Applicants wish to advise the Patent and Trademark Office of the information listed on the attached Form PTO/SB/08 considered during the preparation of the above-identified application. A copy of each of the references listed is enclosed.

Kindly charge any additional fees due, or credit overpayment of fees, to Deposit Account No. 50-0281.

Respectfully submitted,



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Sheet 1 of 2

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Sheet 2 of 2

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OTHER PRIOR ART – NON PATENT LITERATURE DOCUMENTS

Examiner Initials*	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ²
		R. F. FERNSLER ET AL., "Production of large-area plasmas by electron beams," Phys. Plasmas, 1998, 5, 2137-2143	
		WALLACE M. MANHEIMER ET AL., "Theoretical overview of the large-area plasma processing system (LAPPS)," Plasma Sources Sci. Technol. 2000, 9, 370-386	
		S. G. WALTON ET AL., "Ion energy distributions in a pulsed, electron beam-generated plasma," J. Vac. Sci. Technol. A, 2001, 19(4), 1325-1329	
		D. LEONHARDT ET AL., "Plasma diagnostics in large area plasma processing system," J. Vac. Sci. Technol. A, 2001, 19(4), 1367-1373	
		R. A. MEGER ET AL., "Beam-generated plasmas for processing applications," Phys Plasmas, 2001, 8, 2558-2564	
		KARL-HEINZ MULLER, "Stress and microstructure of sputter-deposited thin films: Molecular dynamic investigations," J. Appl. Phys., 1987, 62, 1796-1799	

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